

U.S. Department of Commerce, Patent and Trademark INFORMATION DISCLOSURE STATEMENT BY APPLICANT MAR 05 2004 PATENT & TRADEMARK OFFICE Use several sheets if necessary)				Atty. Docket No. TNCR.196US2		Application No. 10/699,153	
				Applicant(s) Ibrahim Abdulhalim, et al.		Conf. No. 1463	
				Filing Date October 30, 2003		Group 1765	
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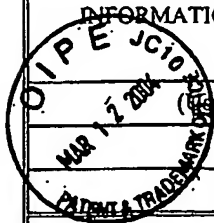
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		Document	Date	Country	Class	Subclass	Yes	No
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